

Multilayer Ceramic Capacitor and Production Method
Thereof

[0001]

5 BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to a
multilayer ceramic capacitor, and particularly
relates to a multilayer ceramic capacitor having a
large capacitance, large capacitance even in a
compact size, and high reliability.

[0002]

2. Description of the Related Art

A gain capacitance of a multilayer ceramic
capacitor is in a relationship of a formula (1)
below.

[0003]

$$C = \varepsilon_0 \cdot \varepsilon_r \cdot n \cdot S / d \quad \dots (1)$$

(C: capacitance (F), ε_0 : vacuum permittivity,
 ε_r : specific permittivity of dielectric material, n:
number of layers, S: valid area, d: thickness of
dielectric)

Accordingly, in order to increase capacitance,
there are methods of making the dielectric layer
thickness d thinner, increasing the specific

permittivity ϵ_r , increasing the valid area S and increasing the number n of dielectric layers.

[0004]

However, since there is a limit in increasing the valid area to obtain a large capacitance in a compact size, a method of increasing the permittivity or making the layer thinner is generally used.

[0005]

Owing to the problem of unevenness of tickness, there has been said that the limit of a thinner dielectric layer was $10\mu\text{m}$ or $5\mu\text{m}$, but a product having a thinner layer than the limit has come to be produced due to development of production techniques.

[0006]

Even if a chip capacitor of an extremely thin layer wherein the dielectric thickness is $3\mu\text{m}$ or less can be produced, however, there arises a disadvantage that it cannot stand a practical use because resistance of the dielectric is too low. Therefore, a method of making a dielectric particle diameter between internal electrodes less than the thickness of a dielectric layer and making the number of dielectric particles between the

electrodes two or more has been taken in the related art. It is for placing a grain boundary phase and securing insulation resistance by making the number of dielectric particles between electrodes two or more. Note that the state that the number of dielectrics between electrodes is two or more means that a straight line drawn vertically from one internal electrode to an internal electrode next to it passes through two or more particles.

[0007]

However, when the layer becomes still thinner and the dielectric thickness becomes $3\mu\text{m}$ or less, it is necessary to make the particle diameter $1.5\mu\text{m}$ or less in order to make the dielectric particles between the internal electrodes two or more, so there has been a disadvantage that the gain capacitance cannot be made larger.

[0008]

Thus, capacitance per volume inevitably becomes small and that has been an obstacle of attaining a compact size and larger capacitance.

[0009]

Note that, as described in the Japanese Unexamined Patent Publication No. 11-317322, a capacitor wherein a particle diameter of about 20%

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[0012]

To attain the above object, according to the present invention, there is provided a multilayer ceramic capacitor comprising internal electrode

layers and dielectric layers, wherein an average
particle diameter (R), in a direction parallel with
the internal electrode layers, in dielectric
particles constituting the dielectric layers is
5 larger than a thickness of the dielectric layer (d).

Note that the average particle diameter of the
dielectric particles in the dielectric layers means
an average particle diameter of the dielectric
particles in the valid dielectric layer (which
10 contribute to the capacitance) between a pair of
internal electrode layers. The average particle
diameter is an average not including dielectric
particles in a dielectric layer of which parts do
not contribute to the capacitance (for example, a
15 dielectric layer arranged on an outer side of the
dielectric layer in the stacking direction not
sandwiched by the internal electrode layers).

[0013]

Preferably, a ratio (R/d) of the average
20 particle diameter (R) and the thickness (d) of the
dielectric layer satisfies $1 < R/d < 3$.

[0014]

Preferably, a main component of the internal
electrode layers is Ni or Cu. In this case, Fe is
25 preferably segregated in the internal electrode

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layers
layers.

[0015]

In the present invention, a multilayer ceramic capacitor of particularly high reliability can be obtained even if the thickness of the dielectric layer is less than $3\mu\text{m}$.

[0016]

In the present invention, a dielectric layer comprises at least the dielectric particle and a grain boundary phase. An area ratio of the grain boundary phase on a section of the dielectric layer is preferably 2% or less.

The dielectric particle may have, for example, a core-shell structure.

In the present invention, preferably, the dielectric layer is comprised of dielectric particles, a grain boundary and grain boundary phase, a segregation phase (second phase) exists in the grain boundary phase, and the segregation phase contains at least two kinds of elements selected from Mn, Y, Si, Ca, V and W.

[0017]

According to the present invention, there is provided a production method of a multilayer ceramic capacitor, comprising the steps of firing a green

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chip to be a capacitor element body comprising dielectric layers and internal electrode layers in a reducing atmosphere; and performing heat processing under an atmosphere of which oxygen partial pressure is higher than the reducing atmosphere; wherein an average particle diameter (R) in a direction parallel with the internal electrode layers in dielectric particles constituting the dielectric layer is made to be larger than a thickness (d) of the dielectric layer.

Preferably, a temperature of heat processing after firing under the reducing atmosphere is 1000°C or more. Also, an oxygen partial pressure at the time of heat processing after firing under the reducing atmosphere is preferably 10^{-3} Pa to 1 Pa.

[0018]

Note that in the present invention, the average particle diameter is defined as below. Namely, when the multilayer ceramic capacitor is cut at a section which is vertical with respect to the internal electrodes and passes both of the external electrodes, a straight line which is substantially parallel with the internal electrode layer is drawn at a center portion between the internal electrodes on this cut section, and when assuming that the

number of particles crossing with this line is n (n is 10 or more), and a length of the line is L , L/n is the average particle diameter (R) in the direction horizontal to the internal electrodes.

5 [0019]

In the present invention, due to the dielectric layer having the above configuration, a highly reliable multilayer ceramic capacitor having large capacitance per a unit volume and a large
10 capacitance even in a compact size can be realized.

[0020]

Also, in the present invention, even if the thickness of the dielectric layer is less than $3\mu\text{m}$, it is possible to obtain capacitance of a high
15 volume ratio of $100\text{F}/\text{m}^3$ or more by obtaining the configuration wherein the largest particle diameter of particles is larger than a distance between the electrodes. This particle diameter can be realized by adjusting a dielectric composition, firing
20 temperature and firing atmosphere. Also, sufficient insulation resistance can be obtained by performing heat processing under an optimal oxygen partial pressure after firing in a reducing atmosphere, so the reliability improves.

25 [0021]

BRIEF DESCRIPTION OF THE DRAWINGS

These and other objects and features of the present invention will become clearer from the following description of the preferred embodiments given with reference to the attached drawings, in which:

Fig. 1 is a schematic sectional view of a multilayer ceramic capacitor according to an embodiment of the present invention; and

Fig. 2 is an enlarged sectional view of a key portion of a dielectric layer shown in Fig. 1.

[0022]

DESCRIPTION OF THE PREFERRED EMBODIMENTS

Multilayer Ceramic Capacitor

As shown in Fig. 1, a multilayer ceramic capacitor 1 according to an embodiment of the present invention comprises a capacitor element body 10 wherein dielectric layers 2 and internal electrode layers 3 are alternately stacked. On the both end portions of the capacitor element body 10 are formed a pair of external electrodes 4 respectively connected to the internal electrode layers 3 alternately arranged inside the element body 10. A shape of the capacitor element body 10 is not particularly limited, but is normally a

rectangular parallelepiped. Also a size thereof is not particularly limited and may be a suitable size in accordance with use, but is normally about (0.6 to 5.6mm)×(0.3 to 5.0mm)×(0.3 to 1.9mm).

5 [0023]

The internal electrode layers 3 are stacked so that the respective end surfaces are alternately exposed to surfaces of facing two end portions of the capacitor element body 10. The pair of external electrodes 4 are formed on the both end portions of the capacitor element body 10 and connected to the exposed end surfaces of the alternately arranged internal electrode layers 3 in order to configure a capacitor circuit.

15 [0024]

Dielectric Layer 2

The composition of the dielectric layer 2 is not particularly limited in the present invention, but for example composed of a dielectric ceramic composition below.

A dielectric ceramic composition of the present embodiment contains, for example, a main component expressed by $\{(Ba_{(1-x-y)} Ca_x Sr_y)O\}_A (Ti_{(1-z)} Zr_z)_B O_2$. Note that A, B, x, y and z are in any range but preferably, for example, $0.990 \leq A/B \leq 1.010$, $0 \leq x \leq 0.80$,

0≤y≤0.5, 0.01≤z≤0.98. As subcomponents contained together with the main component in the dielectric ceramic composition, a subcomponent containing at least one kind selected from oxides of Y, Gd, Tb, Dy, V, Mo, Zn, Cd, Sn, W, Ca, Mn, Si and P can be mentioned as an example.

[0025]

By adding the subcomponent, a low temperature firing becomes possible without declining dielectric characteristics of the main component, deficiency in reliability at the time of making the dielectric layer thinner can be reduced and a longer durability can be attained. Note that in the present invention, the composition of the dielectric layer is not limited to the above.

[0026]

Note that the conditions of the number and thickness, etc. of layers of the dielectric layer 2 shown in Fig. 1 may be suitably decided in accordance with an object and use, but according to the present embodiment, the thickness of the dielectric layer is 6μm or less, preferably 3μm or less, further preferably less than 2μm.

[0027]

As shown in Fig. 2, the dielectric layer 2

comprises at least dielectric particles 2a and a grain boundary phase 2b. The area ratio of the grain boundary phase 2b on the section of the dielectric layer 2 is preferably 2% or less. The dielectric particle 2a, for example, has a core-shell structure. The grain boundary phase has its components oxides of a material constituting dielectric materials or internal electrode materials, oxides of separately added materials, and furthermore, oxides of materials to be mixed as impurities during the processing. The grain boundary phase 2b contains at least two kinds of segregated substances (segregated phase (a second phase)) selected from Mn, Y, Si, Ca, V and W.

[0028]

In the present embodiment, an average particle diameter R in the direction H which is parallel with the internal electrode layers 3 in the dielectric particles 2a constituting the dielectric layer 2 is larger than the dielectric layer thickness d, and the ratio (R/d) between the average particle diameter R and the dielectric layer thickness d is preferably $1 < R/d < 3$. Note that the larger the ratio of the average particles diameter R with respect to the dielectric layer thickness d, the larger the

5 Note that the average particle diameter of the
dielectric particles 2a in the dielectric layer 2
means an average particle diameter of the dielectric
particles 2a in the dielectric layers 2 (which
contribute to the capacitance) sandwiched between
10 the internal electrode layers 3. The average
particle diameter is an average not containing
dielectric particles in the dielectric layer of
which parts do not contribute to the capacitance
(for example, a dielectric layer arranged on an
15 outer side in the stacking direction of the
dielectric layer 2a not sandwiched between the
internal electrode layers 3). The dielectric
particles 2a contact both of the pair of internal
electrode layers 3 sandwiching the dielectric
20 particles 2a.

Note that the average particle diameter R is defined as below. Namely, when assuming that a straight line H which is substantially parallel with the internal electrode layer is drawn at a center

portion of the internal electrodes 3 on the cut section shown in Fig. 2, the number of particles crossing with this line is n (n is 10 or more), and a length of the line is L , L/n is the average particle diameter (R) in the direction horizontal to the internal electrodes 3.

[0030]

Internal Electrode Layer 3

A conductive material contained in the internal electrode layer 3 is not particularly limited, but since the material composing the dielectric layer 2 has reduction resistance characteristics, a base metal can be used. As a base metal used as a conductive material, Ni, Cu, Ni alloy or Cu alloy is preferable. When a main component of the internal electrode layer 3 is Ni, a method of firing in a low oxygen partial pressure (reducing atmosphere) is taken so as not to reduce the dielectric. On the other hand, a method of making the composition ratio a little different from the stoichiometric composition so as not to reduce the dielectric.

The thickness of the internal electrode layer 3 may be suitably determined in accordance with a use, but is normally 0.5 to $5\mu\text{m}$, in particularly, about 1 to $2.5\mu\text{m}$.

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The paste for dielectric layer may be an

organic-based paint obtained by mixing a dielectric material and organic vehicle, or a water-based paint.

As the dielectric material, materials constituting the main component, materials constituting the subcomponent and materials constituting sintering aids in accordance with need are used in accordance with the composition of the dielectric ceramic composition explained above. As materials constituting the main component, oxides of Ti, Ba, Sr, Ca, Zr and/or a compound which become the oxide by firing are used. As the material constituting the subcomponent, a single oxide or composite oxide of at least one kind, preferably three kinds or more selected from oxides of Sr, Y, Gd, Tb, Dy, V, Mo, Zn, Cd, Ti, Ca, Sn, W, Mn, Si and P and/or a compound which becomes the oxide by firing is used.

[0034]

In the production method according to the present invention, sintering aids are not necessarily contained, but in the case of containing the same, for example, oxides of Si or Li and/or a compound which becomes the oxide by firing is used.

As the compound which becomes the oxide by firing,

for example, carbonate, nitrate, oxalate, organic metal compounds, etc. may be mentioned. Of course the oxide and compound which becomes the oxide by firing may be used together.

5 For powders of these materials, those having an average particle diameter of about 0.005 to 5 μ m is normally used. A dielectric material can be obtained from the material powders, for example, by conducting as described below.

10 [0035]

First, starting materials are combined to have a predetermined amount ratio and wet-mixing is conducted, for example, by using a ball-mill, etc. Next, it is dried by a spray dryer, etc., then, 15 calcined, and the dielectric oxide of the above formula constituting the main component is obtained. Note that the calcination is performed normally at 500 to 1300°C, preferably at 500 to 1000°C and more preferably at 800 to 1000°C for about 2 to 10 hours 20 in an air. Next, it is grinded to have a predetermined particle diameter by a jet-mill or ball-mill, etc. to obtain the dielectric material. The subcomponent and sintering aids (SiO₂ or Li₂O, etc.) are respectively calcined separately from the 25 main component and mixed into the obtained

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dielectric material. If the subcomponent is calcined together with the calcination of the main component, desired characteristics cannot be obtained.

[0036]

5 Additives, such as binders, plasticizers, dispersants, solvents, etc. used at the time of adjusting the dielectric layer paste may be various. Also, glass frit may be added to the dielectric layer paste. As the binder, ethyl cellulose, abietic acid resin, polyvinyl butyral, etc. may be
10 mentioned, as the plasticizer, for example, abietic acid derivative, diethyl oxalate, polyethylene glycol, polyalkylene glycol, phthalic acid ester, phthalic acid dibutyl, etc., as the dispersant, for
15 example, glycerin, octadecylamine, trichloroacetic acid, oleic acid, octadiene, oleic acid ethyl, mono oleic acid glycerin, tri oleic acid glycerin, tristearic acid glycerin, mencedene oil, etc., and
20 as the solvent, for example, toluene, terpeneol, butyl carbitol, methylethylketone, etc. may be mentioned. When firing the paste, it is made that the dielectric material accounts for about 50 to 80wt% in the whole paste, the binder accounts for 2 to 5wt%, the plasticizer accounts for 0.01 to 5wt%,
25 the dispersant accounts for 0.01 to 5wt%, and the

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5 [0037]

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As the conductive material used at the time of preparing the internal electrode paste, Ni, Ni alloy, furthermore, mixture of these are used. Such conductive materials are sphere shaped, scale

shaped, etc. and the shape is not particularly limited and may be mixture of these shapes. Also, the conductive materials having the average particle diameter of about 0.1 to 10 μ m, preferably about 0.2 to 1 μ m may be normally used.

[0040]

The organic vehicle contains a binder and solvent. As the binder, any of well-known ones can be used, for example, ethyl cellulose, acrylic resin, butyral resin, etc. A content of the binder is made to be about 1 to 5wt%. As the solvent, any of well-known ones can be used, for example, terpionel, butyl carbitol, kerosene, etc. A content of the solvent is made to be about 20 to 55wt% with respect to the whole paste.

[0041]

Thus obtained internal electrode layer paste and the dielectric layer paste are alternately stacked by using a printing method, transfer method, green sheet method, etc. When using the printing method, the dielectric layer paste and the internal electrode layer paste are successively printed on a PET or other substrate, cut into a predetermined shape, then, peeled from the substrate to form a stacked body. While, when using the sheet method,

the dielectric layer paste is used to form a green sheet (dielectric layer before firing), and an internal electrode pattern (internal electrode layer before firing) comprised of the internal electrode layer paste is printed thereon.

[0042]

A large number of the green sheets being printed the internal electrode pattern thereon are stacked in the stacking direction to form a stacked body. On the uppermost end and the lowermost end thereof in the stacking direction are also stacked a plurality of green sheets on which the internal electrode pattern is not printed.

[0043]

Next, thus obtained stacked body is cut into a predetermined size of the stacked body to form a green chip, then, binder removal processing and firing are performed. Heat processing is then performed to re-oxidize the dielectric layer 2.

[0044]

The binder removal processing may be performed under normal conditions, but if Ni, Ni alloy or other base metal is used for the conductive material of the internal electrode layers, the processing is preferably performed under the following conditions.

[0045]

Rate of temperature rise: 5 to 300°C/hour, in particular 10 to 50°C/hour

Holding temperature: 200 to 400°C, in particular 250 to 350°C

Temperature holding time: 0.5 to 20 hours, in particular 1 to 10 hours

Atmosphere: in a wet mixed gas of N₂ and H₂

[0046]

Firing is preferably performed under the conditions below.

Rate of temperature rise: 50 to 500°C/hour, in particular 200 to 300°C/hour

Holding temperature: 1100 to 1300°C, in particular 1150 to 1250°C

Temperature holding time: 0.5 to 8 hours, in particular 1 to 3 hours

Cooling rate: 50 to 500°C/hour, in particular 200 to 300°C/hour

Atmospheric gas: a wet mixed gas of N₂ and H₂, etc.

[0047]

Note that the oxygen partial pressure in the air atmosphere is preferably 10⁻² Pa or less, in particular 10⁻² to 10⁻⁸ Pa. When exceeding the above

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range, the internal electrode layer is liable to be oxidized, while when the oxygen partial pressure is too low, the electrode material of the internal electrode layer is liable to result in abnormal sintering and break off.

[0048]

The heat processing after the above firing is preferably performed by setting the holding temperature or the highest temperature preferably at 1000°C or more, in particular 1000 to 1100°C. If the holding temperature or the highest temperature during the heat processing is less than the above range, oxidization of the dielectric material becomes insufficient so the insulation resistance lifetime tends to become short. On the other hand, when the holding temperature exceeds the above range, Ni of the internal electrode is oxidized and not only do capacitance fall, but also the internal electrode layers end up reacting with the dielectric material resulting in a tendency toward a fall in the lifetime. The oxygen partial pressure at the time of the heat processing is higher than the reducing atmosphere at the time of firing and preferably is 10^{-3} Pa to 1 Pa, more preferably, 10^{-2} pa to 1Pa. When the oxygen partial pressure is less

than the above range, reoxidization of the dielectric layer 2 is difficult, while when over that range, the internal electrode layer 3 tends to oxidize. Other heat processing conditions are preferably as below.

[0049]

Temperature holding time: 0 to 6 hours, in particular 2 to 5 hours

Cooling rate: 50 to 500°C/hour, in particular 100 to 300°C/hour

Atmospheric gas: wet N₂ gas, etc.

[0050]

Note that, for example, a wetter, etc. may be used to wet the N₂ gas and mixed gas, etc. In this case, the temperature of the water is preferably about 0 to 75°C. Also, the binder removal processing, firing and heat processing may be performed consecutively or independently. When performing these consecutively, preferably, after the binder removal processing, the atmosphere is changed without cooling, then the temperature is raised to the holding temperature for firing, the firing is performed, then cooled, and the atmosphere is changed when the holding temperature of the heat processing is reached, and then the heat processing

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is performed. On the other hand, when performing these independently, at the time of firing, preferably the temperature is raised to the holding temperature at the time of the binder removal processing in an N_2 gas or wet N_2 gas atmosphere, then the atmosphere is changed and the temperature is further raised. After the temperature is cooled to the holding temperature at the time of the heat processing, the atmosphere is changed again to N_2 gas or wet N_2 gas atmosphere and the cooling continues. Further, at the time of annealing, the temperature may be raised to the holding temperature in an N_2 gas atmosphere, then the atmosphere changed or the entire annealing process may be performed in a wet N_2 gas atmosphere.

[0051]

The thus obtained sintered body (element body 10) is, for example, end polished, for example, using barrel polishing or sandblasting etc., then an external electrode paste is fired thereon to form the external electrodes 4. The firing conditions of the external electrode paste are for example preferably 600 to 800°C for 10 minutes to 1 hour or so in a wet mixed gas of N_2 and H_2 . Further, in accordance with need, the surfaces of the external

electrodes 4 may be subjected to plating, etc. to form a pad layer. Note that the external electrode paste may be prepared in the same way as preparing the above internal electrode paste.

5 The thus produced multilayer ceramic capacitor of the present invention is mounted on a print substrate, etc. by soldering, etc. and used in a variety of electric devices, etc.

10 In the present embodiment, by optimizing the dielectric composition, the firing conditions and heat processing conditions after firing, even if the thickness of the dielectric layer is less than $3\mu\text{m}$ and the particle diameter is larger than the dielectric thickness, sufficient insulation
15 resistance can be obtained.

 Note that the present invention is not limited to the above embodiments and a variety of modifications can be made within the scope of claims of the present invention.

20 [0052]

 Below, the present invention will be explained based on further detailed examples, but the present invention is not limited to this examples.

 [0053]

25 Example 1

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As starting materials, BaTiO_3 and BaZrO_3 produced by liquid phase synthesis method were used. Note that an average particle diameter of the BaTiO_3 and BaZrO_3 was $0.5\mu\text{m}$ and the largest particle diameter was $1.5\mu\text{m}$. The composition of the main composition was set to be as indicated in the formula below.

[0054]

Namely, the main composition is $\text{Ba}_{1.005}(\text{Ti}_{0.81}\text{Zr}_{0.19})\text{O}_3$. With respect to the main composition, 0.20wt% of MnCO_3 , 0.30wt% of Y_2O_3 , 0.04wt% of V_2O_5 , 0.05wt% of WO_3 and 0.2wt% of SiO_2 (an average particle diameter is $1.0\mu\text{m}$ and the largest particle diameter is $3.3\mu\text{m}$ in the entire additives) are respectively wet-mixed by using a ball-mill for 16 hours to obtain dielectric materials. The thus obtained dielectric materials in a blending ratio described below are mixed by using zirconia ball-mill, made to be slurry and to be a dielectric layer paste. Namely, the blending ratio is 100 parts by weight of dielectric material, 5.0 parts by weight of acrylic resin, 2.5 parts by weight of phthalic acid benzyl butyl, 6.5 parts by weight of mineral spirits, 4.0 parts by weight of acetone, 20.5 parts by weight of trichloroethane and 41.5 parts by

weight of methylene chloride.

[0055]

Next, the materials in the blending ratio described below were kneeled by using a three-roll, made to be slurry and to be an internal electrode paste. Namely, 44.6 parts by weight of Ni, 52 parts by weight of terpionel, 3 parts by weight of ethyl cellulose and 0.4 parts by weight of benzotriazol were blended. These pastes were used for producing the multilayer ceramic chip capacitor 1 shown in Fig. 1 in the following way.

[0056]

First, the dielectric layer paste was used for forming a sheet having a thickness of $3.5\mu\text{m}$ on a carrier film by using a doctor blade method, etc. and the internal electrode paste was used for printing an internal electrode pattern thereon. Then, the above sheet is peeled from the carrier film, a plurality of sheets on which the internal electrode is printed are stacked and adhered by pressure. Note that the number of stacked layers was 100 in the dielectric layer 2. Next, after cutting the stacked body into a predetermined size, the binder removal processing, firing and heat processing were consecutively performed under the

following conditions.

[0057]

Binder Removal Processing

Rate of temperature rise: 20°C/hour

5 Holding temperature: 300°C

Temperature holding time: 2 hours

Atmospheric gas: in the air

[0058]

Firing

10 Rate of temperature rise: 200°C/hour

Holding temperature: 1150°C

Temperature holding time: 2 hours

Cooling rate: 300°C/hour

Atmospheric gas: a wet mixed gas of N₂ and H₂

15 Oxygen partial Pressure: 10⁻³ Pa

[0059]

Heat Processing

Holding temperature: 1100°C

Temperature holding time: 3 hours

20 Cooling rate: 300°C/hour

Atmospheric gas: a wet gas of N₂

Oxygen partial Pressure: 10⁻² Pa

[0060]

Note that a wetter is used to wet the
25 respective atmospheric gases and the temperature of

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the water was 0 to 75°C.

[0061]

After polishing the end surface of the thus
obtained sintered body by sandblasting, an In-Ga
5 alloy is applied to form a test-use electrode. A
size of the multilayer capacitor produced in this
way was 3.2mm×2.5mm×1.6mm, the thickness of the
dielectric layer 2 was 2.3 μ m and the thickness of
the internal electrode layer 3 was 1.5 μ m.

10 [0062]

Samples of the multilayer capacitor of the
present example were measured as below.

Measurement was conducted after 24 hours left
after one hour of heat processing at 150°C to
15 measure the initial characteristics. An impedance
analyzer (HP4284A) was used for measure capacitance
and loss coefficient at 1 KHz and 1V. The insulation
resistance was measured by using a high ohm-meter
R8340 under a condition of 10V. Also, an average
20 particle diameter of the dielectric particles was
observed as described below.

[0063]

The multilayer ceramic capacitor was cut by a
section vertical to the internal electrode which
25 passes both terminal electrodes, the section was

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polished, and the polished section was observed by
microscope. At the center portion between the
internal electrode layers on the polished section, a
straight line H (refer to Fig. 2) was drawn in
5 parallel with the internal electrode layers. When
assuming that the number of particles crossing with
the line H was n and the length of the line was L ,
 L/n was considered as the particle diameter (R) in
the direction horizontal to the internal electrode
10 layers.

Measurement results of the average particle
diameter (R) of the dielectric particles, the ratio
(R/d) between the average particle diameter and the
dielectric layer thickness d , capacitance (C/V) per
15 a unit volume and product (CR) of the capacitance
and insulation resistance are shown in Table 1.

20

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[0064]

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Table 1

	firing temperature	dielectric layer thickness d (μm)	average particle diameter R (μm)	R/d	C/V (F/m ³)	CR (M $\Omega\mu\text{F}$)
example 1	1150°C	2.3	3	1.3	375	4620
example 2	1100°C	2.3	2.5	1.09	363	5350
example 3	1200°C	4.2	5.4	1.29	143	2800
example 4	1150°C	4.2	4.5	1.07	129	3120
comparative example 1	1125°C	4.2	4.2	1	98	3230
comparative example 2	1100°C	4.2	3.8	0.9	93	3450
example 5	1200°C	5.8	6	1.03	75	2170
comparative example 3	1150°C	5.8	4.5	0.78	69	2500
comparative example 4	1100°C	5.8	3.8	0.66	59	3030

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[0065]

Example 2

As shown in Table 1, a sample of a capacitor was prepared in the same way as in the example 1 except that the firing temperature was made to be 1100°C, and results of the same measurement is shown in Table 1.

[0066]

Example 3

As shown in Table 1, a sample of a capacitor was prepared in the same way as in the example 1 except that the firing temperature was made to be 1200°C and that the dielectric layer thickness was made to be 4.2μm, and results of the same measurement is shown in Table 1.

[0067]

Example 4

As shown in Table 1, a sample of a capacitor was prepared in the same way as in the example 1 except that the firing temperature was made to be 1150°C and that the dielectric layer thickness was made to be 4.2μm, and results of the same measurement is shown in Table 1.

[0068]

As shown in Table 1, a sample of a capacitor

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was prepared in the same way as in the example 1
except that the firing temperature was made to be
1200°C and that the dielectric layer thickness was
made to be 5.8 μ m, and results of the same
measurement is shown in Table 1.

[0069]

Comparative Example 1

As shown in Table 1, a sample of a capacitor
was prepared in the same way as in the example 1
except that the firing temperature was made to be
1125°C, the heat processing temperature after firing
was made to be 1000°C, the oxygen partial pressure
at the time of heat processing was made to be 10⁻²
Pa, and the dielectric layer thickness was made to
be 4.2 μ m, and results of the same measurement is
shown in Table 1.

[0070]

Comparative Example 2

As shown in Table 1, a sample of a capacitor
was prepared in the same way as in the example 1
except that the firing temperature was made to be
1100°C, the heat processing temperature after firing
was made to be 1000°C, the oxygen partial pressure
at the time of heat processing was made to be 10⁻²
Pa, and the dielectric layer thickness was made to

be $4.2\mu\text{m}$, and results of the same measurement is shown in Table 1.

[0071]

Comparative Example 3

As shown in Table 1, a sample of a capacitor was prepared in the same way as in the example 1 except that the firing temperature was made to be 1150°C , the heat processing temperature after firing was made to be 1000°C , the oxygen partial pressure at the time of heat processing was made to be 10^{-2} Pa, and the dielectric layer thickness was made to be $5.8\mu\text{m}$, and results of the same measurement is shown in Table 1.

[0072]

Comparative Example 4

As shown in Table 1, a sample of a capacitor was prepared in the same way as in the example 1 except that the firing temperature was made to be 1100°C , the heat processing temperature after firing was made to be 1000°C , the oxygen partial pressure at the time of heat processing was made to be 10^{-2} Pa, and the dielectric layer thickness was made to be $5.8\mu\text{m}$, and results of the same measurement is shown in Table 1.

[0073]

Evaluation

As is known from comparing the examples 1 to 5 and comparative examples 1 to 4, when the average particle diameter R in the direction parallel with the internal electrode layers is larger than the dielectric layer thickness d in the dielectric particles ($R/d > 1$), it was confirmed that a highly reliable multilayer ceramic capacitor wherein capacitance per unit volume (C/V) is large having a large capacitance even in a compact size can be realized.

[0074]

Also, as shown in the examples 1 and 2, it was confirmed even if the dielectric layer thickness d is less than $3\mu\text{m}$, a capacitance of a high volume ratio of $100\text{F}/\text{m}^3$ or more can be obtained by the structure wherein the largest particle diameter of the particles is larger than a distance between electrodes. Furthermore, as shown in the examples 1 to 5, it was confirmed that by performing heat processing under an optimal oxygen partial pressure after firing in a reducing atmosphere, a sufficient CR product can be obtained, a sufficient insulation resistance R can be attained and the reliability improves.